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TITLE: ALIGNMENT APPARATUS

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INVENTOR-INFORMATION:

NAME	COUNTRY
NISHI, TAKECHIKA	

ASSIGNEE-INFORMATION:

NAME	COUNTRY
NIPPON KOGAKU KK	N/A

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ABSTRACT:

PURPOSE: To make an ideal off-axis alignment free from offset possible, by performing the fine alignment of a reticle and a wafer applying an alignment optical system fixed with respect to a base.

CONSTITUTION: A mounting stand on which a photo-sensitive substrate is mounted is capable of two-dimensional movement, and marks for alignment formed on the back surface of the photo-sensitive substrate can be observed by an alignment optical system. On the other part of the mounting

stand than the mounting part of the photo-sensitive substrate, an optical pass-length calibration means is provided. The focal position of the alignment optical system is calibrated by an amount nearly corresponding with the thickness of photo-sensitive substrate, and a transferred image on the surface of photo-sensitive substrate on the mounting stand can be observed by the alignment optical system. According to such a means, the alignment optical system is capable of observing both of the transferred image formed on the surface of photo-sensitive substrate and the marks formed on the back surface of photo-sensitive substrate. Alignment accuracy can be increased, and matching between alignment systems can be easily attained, thereby.

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